

Supporting Information

Revealing Structure–Activity Links in Hydrazine Oxidation: Doping and Nanostructure in Carbide-Carbon Electrocatalysts

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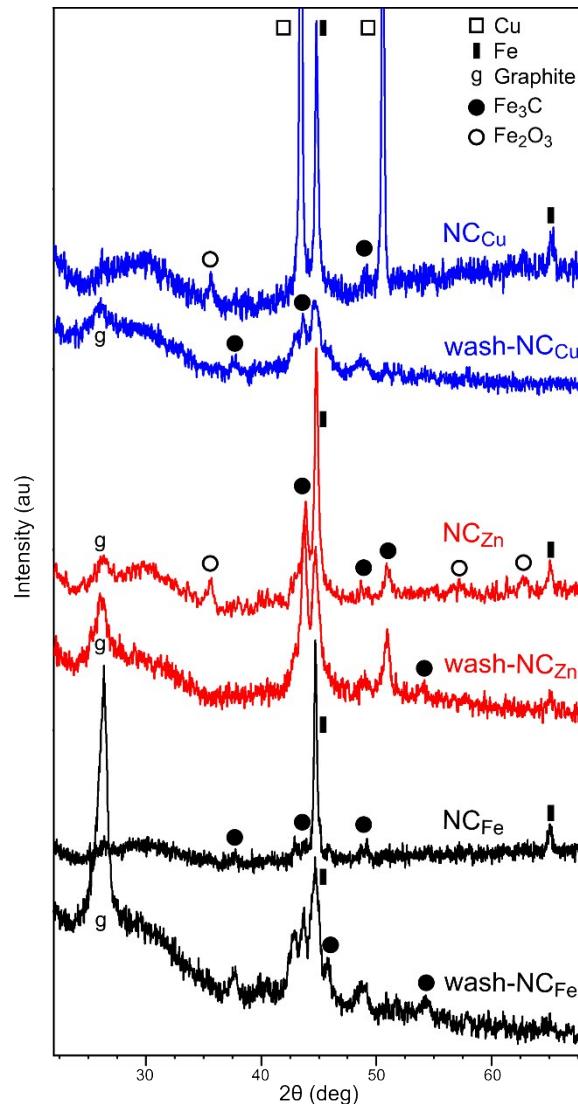


Figure S1. X-ray diffractograms of NCM and wash-NCM (M = Cu, Zn, Fe).

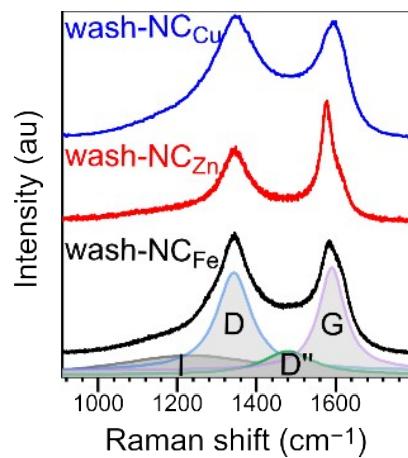


Figure S2. Raman spectra of wash-NC_M (M=Cu, Zn, Fe), with deconvolution demonstrated for wash-NC_{Fe}.

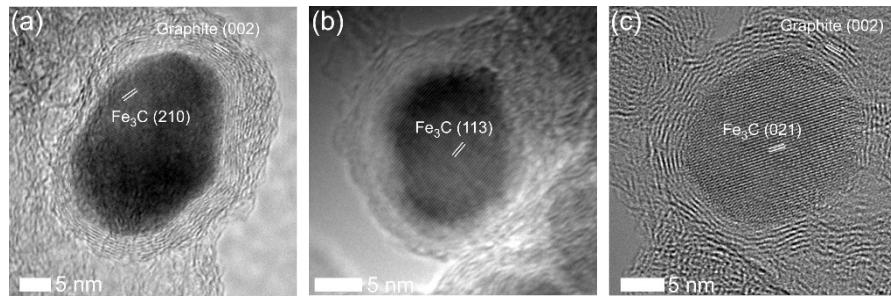


Figure S3. HRTEM images with crystalline Miller indices, analysed by d-spacing for (a) wash-NC_{Fe} (b) wash-NC_{Zn} (c) wash-NC_{Cu}

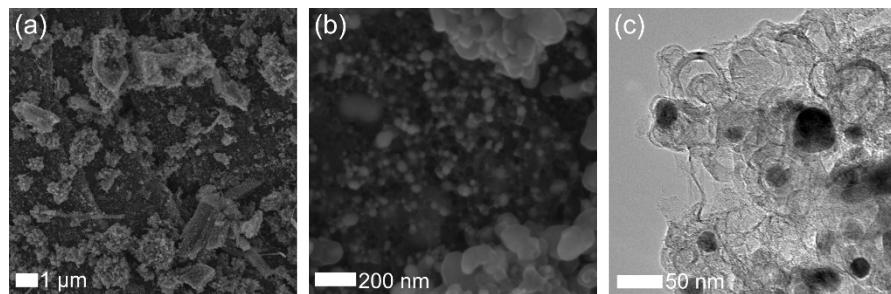


Figure S4. (a) HRSEM of wash-NC_{Fe}, x10K. (b) HRSEM of wash-NC_{Fe}, x200K. (c) HRTEM of wash-NC_{Fe}.

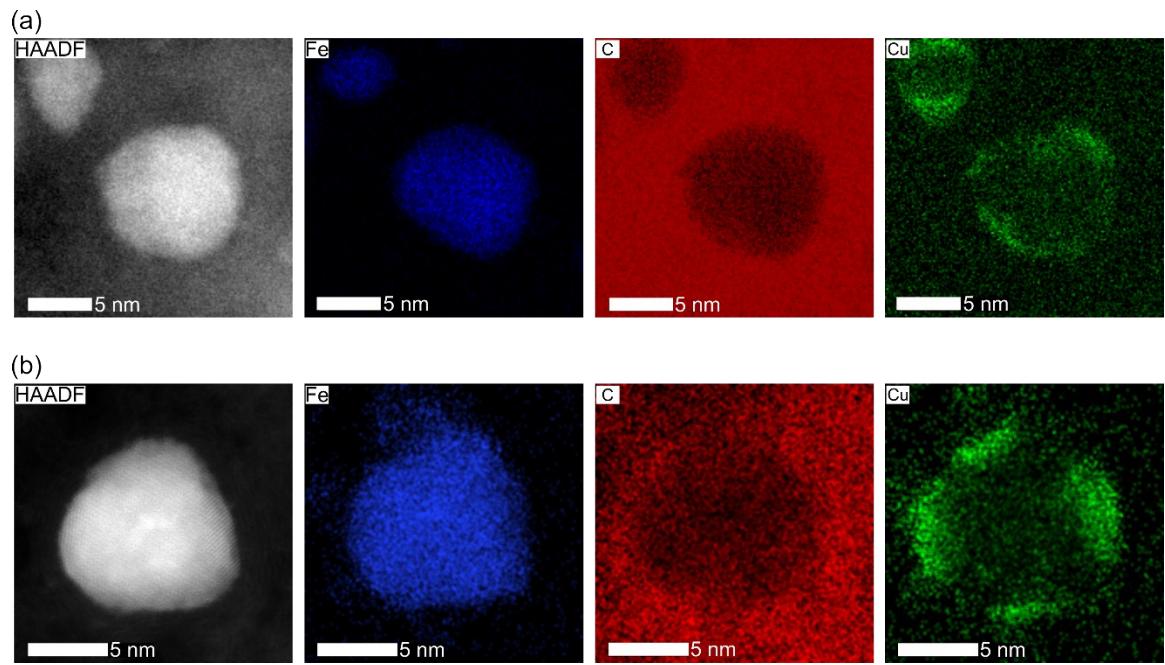


Figure S5. Single-particle elemental mapping images of (a) NC_{Cu} ; (b) wash- NC_{Cu} .

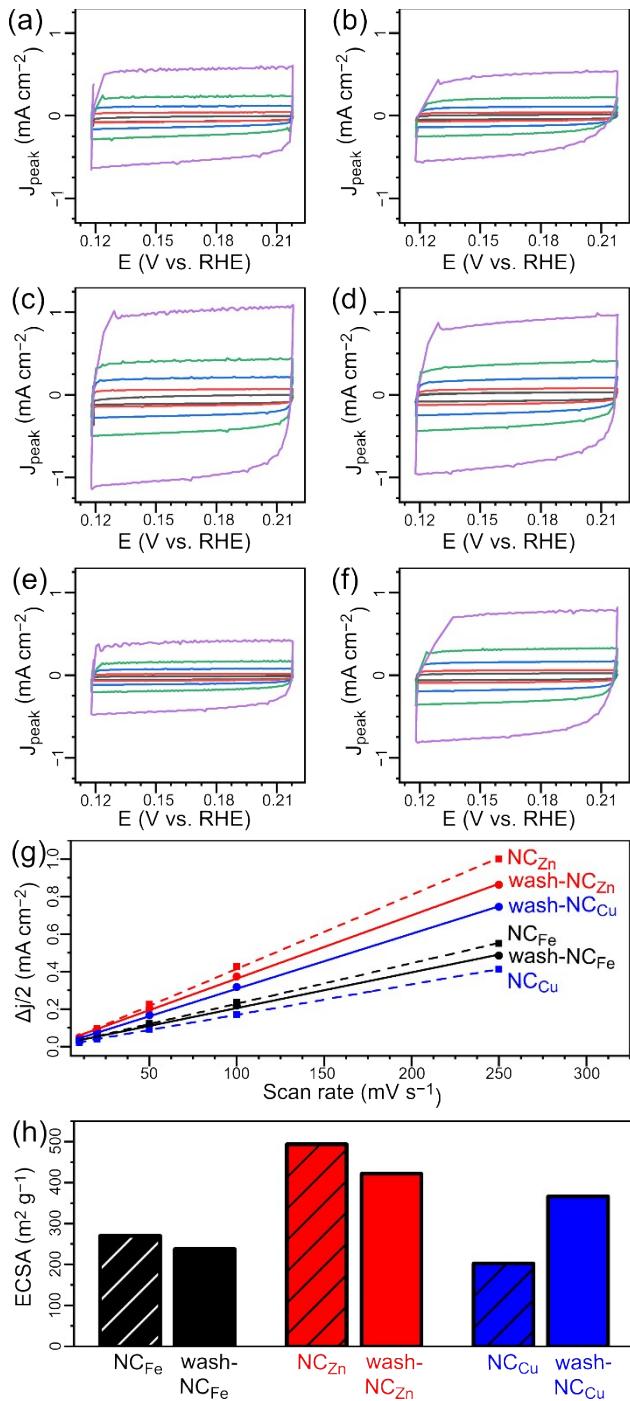


Figure S6. CV of pure double-layer charging (no N_2H_4) of (a) NC_{Fe} (b) wash- NC_{Fe} (c) NC_{Zn} (d) wash- NC_{Zn} . (e) NC_{Cu} (f) wash- NC_{Cu} . (g) Double-layer charging vs. scan rate at 0.168 V vs. RHE. (h) Electrochemical surface area (ECSA) before and after washing. NC_{Fe} and NC_{Zn} show similar ECSA after washing, while NC_{Cu} has a near two-fold increase. The trends are similar to SSAs derived from N_2 porosimetry (Figure 7), except for the increase in SSA in NC_{Fe} after washing, possibly arising from micropores accessible to N_2 yet not to solution. The large differences between BET SSA and ECSA values are due to multi-layer charging in ECSA experiments, while BET SSA is calculated for a single N_2 monolayer.

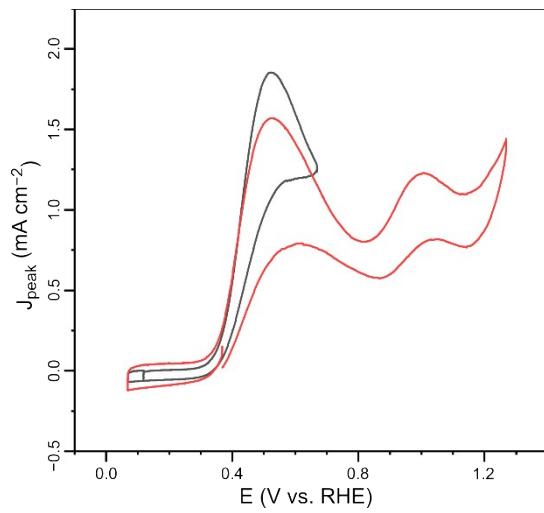


Figure S7. CV of HzOR on wash-NC_{Fe} at extended potential range. 20 mM N₂H₄, 1M KOH, 10 mV s⁻¹.

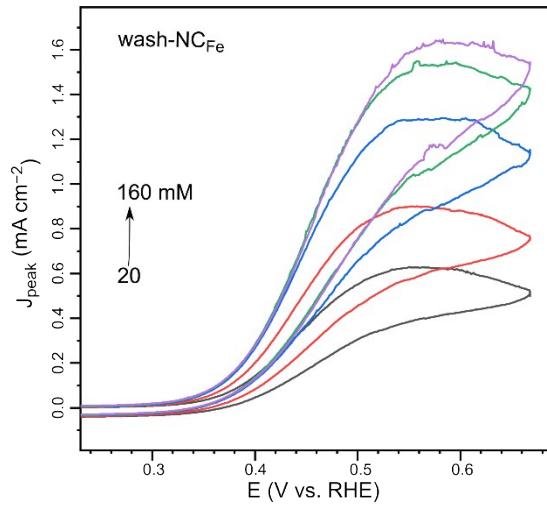


Figure S8. CV of HzOR on wash-NC_{Fe} at varied N₂H₄ concentrations on wash-NC_{Fe}. 1M KOH, [20, 40, 80, 100, 160 mM], 10 mV s⁻¹.

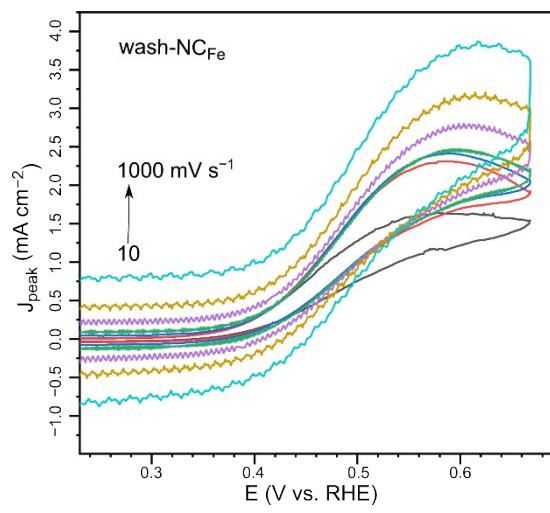


Figure S9. Cyclic voltammetry of HzOR at varied scan rates on wash-NC_{Fe}. 1M KOH, [10, 20, 50, 100, 250, 500, 1000 mV s⁻¹], 160 mM N₂H₄.

Catalyst	Electrolyte	$E_{\text{onset}} \text{ vs. RHE}$	Ref.
wash-NC _M (M=Cu, Zn, Fe)	1 M KOH	0.28	This work
Cu ₃ P on Cu foam	1 M KOH	0.00	1
FeP on Ni foam	1 M KOH	0.00	2
Fe ₂ MoC on NC	1 M KOH	0.28	3
Metal-free, alkaline-earth-derived NC	1 M KOH	0.34	4
'Tree-bark'-structured NC	1 M KOH	0.40	5
Fe ₂ O ₃ on C	1 M KOH	0.50	6
Cu on graphene	0.1 M KOH	0.55	7
Graphene 'nano-hills'	0.1 M KOH	0.64	8
Cu NPs on C	0.1 M KOH	0.71	9
Cu cubes on graphene	0.1 M KOH	0.81	10
Fe@Cu-P on C	0.1 M KOH	0.81	11
CuO nanoshapes on C	0.1 M KOH	0.86	12
CuO nanocrystals on C	0.1 M KOH	0.91	13
Ni- or Co-based			
NiCo pompoms	1 M KOH	-0.19	14
Ni ₆₀ Co ₄₀ on C	1 M KOH	-0.15	15
NiZn on C	1 M KOH	-0.10	16
Ni _{0.5} Co _{0.5} Se ₂ on C	1 M KOH	-0.10	17
Ni-B film	1 M NaOH	-0.09	18
NiMo on C	1 M KOH	-0.08	19
NiMn, NiFe, NiZn on C	1 M KOH	-0.05	20
Ni ₂ P array	1 M KOH	-0.05	21
Ni-Zn on GO	1 M NaOH	-0.05	22
CoP on Ti mesh	1 M KOH	-0.05	23
Co@CoO	1 M KOH	-0.03	24
Ni NPs on C	0.1 M NaOH	0.00	25
Ni-B on C	1 M KOH	0.00	26
Ni-Zn on Ni foam	1 M NaOH	0.00	27
NiCoSe ₂ on Ni foam	0.5 M KOH	0.31	28
Ni ₃ S ₂ on Ni foam	0.1 M KOH	0.86	29
Co-Mo alloys	1 M NaOH	0.90	30
Noble metal-based			
Pd-Rh on NC	1 M KOH	-0.03	31
Pt-NiO _x on C	1 M NaOH	0.00	32
Pd on Ni foam	1 M NaOH	0.00	33
Ag on g-C ₃ N ₄	0.1 M NaOH	0.51	34
Ag on Zn-based MOF	0.1 M NaOH	0.61	35
Au on TiO ₂	0.1 M KOH	0.70	36
Cu-Pd-O _x	0.1 M KOH	0.9	37

Table S1. HzOR electrocatalysis at alkaline pH. Catalysts that are non-supported on a carbon matrix are grouped separately and colored grey, since carbon supports are

useful for dispersion, support, and conductivity enhancement of the catalysts (aspects not expressed by the onset potential). C and NC stand for carbon and nitrogen-doped carbon, respectively.

Material	C at%	N at%	O at%	Fe at%	M at% (=Cu, Zn)
NC_{Fe}	89.9	1.7	7.3	1.1	
wash-NC_{Fe}	95.3	1.6	2.6	0.5	
NC_{Zn}	90.4	3.1	5.7	0.8	0
wash-NC_{Zn}	92.9	3.1	3.4	0.6	0
NC_{Cu}	86.3	2.1	8.2	1.7	1.6
wash-NC_{Cu}	84.2	1.9	10.8	1.4	1.4

Table S2. XPS results for NC_M and wash-NC_M (M=Cu, Zn, Fe). The values are within $\pm 0.4\%$, based on peak integration error.

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